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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re U.S. Patent Application of:

INVENTORS: Alan Edward Rosenbluth

SERIAL NO.: 10/727,901

ART UNIT: 2851

FILED: 12/4/2003

EXAMINER: Unknown

TITLE: Printing A Mask With Maximum Possible Process Window Through Adjustment
Of The Source Distribution

ATTORNEY DOCKET NO.: YOR920030339US1

Commissioner For Trademarks

P.O. Box 1450

Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Pursuant to Sections 609 and 707.05(b) of the MPEP and 37 CFR 1.97-1.99, the attached form PTO-1449 lists documents, which may be pertinent to the invention as claimed in the above-identified application. Copies are herewith submitted of the non-U.S. documents and publications. .

The citation of these documents should not be construed as a representation that a thorough search has been made, or that other, more pertinent material is not available.

Respectfully submitted,


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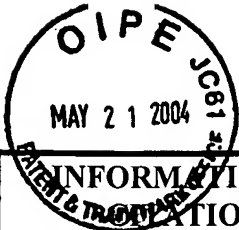
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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail on the date shown below in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

5/19/2004
Date

Claine F. Mian
Name of Person Making Deposit



INFORMATION DISCLOSURE CITATION FORM FOR PATENT APPLICATION (FORM PTO-1449) (Substitute)	Docket No.: YOR920030339US1	Serial No.: 10/727,901
	Applicant(s): Alan Edward Rosenbluth	
	Filing Date: 12/4/2003	Group: 2851

U.S. PATENT DOCUMENTS

Examiner Initials	Document Number (Number-Kind Code)	Publication Date (MM-DD-YYYY)	Name of Patentee or Applicant	Class	Sub-class
	US-5,680,588	10-21-1997	Gortych et al.	395	500
	US-6,563,566 B2	05-13-2003	Rosenbluth et al.	355	67
	US-				
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FOREIGN PATENT DOCUMENTS

Examiner Initials	Document Number (Country Code-Number-Kind Code)	Publication Date (MM-DD-YYYY)	Name Of Patentee of Applicant	Translation? Yes/No/n/a
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OTHER DOCUMENTS (Author (Capitalize), Title, Date, Pages, Etc., if known)

	M. Burkhardt, et al., "Illuminator design for the printing of regular contact patterns," Microelectronic Engineering 41-42 (1998); p. 91
	T.-S. Gau, et al., "The Customized Illumination Aperture Filter for Low k1 Photolithograph Process," SPIE v. 4000 – Optical Microlithography XIII, (2000): p. 271
	A. E. Rosenbluth, et al., "Optimum Mask and Source Patterns to Print a Given Shape," Journal of Microlithography, Microfabrication, and Microsystems v.1, no. 1 (2002): P. 13
	R. Socha, et al., "Illumination optimization of periodic patterns for maximum process window," Microelectronic Engineering 61-62 (2002): p. 57
	A. K. Wong, et al., "Level-specific lithograph optimization for 1-Gb DRAM," IEEE Transactions on Semiconductor Manufacturing 13, no. 1 (Feb. 2000): p. 76
	M. Born et al., Principles of Optics, 5 ed. (Oxford: Pergamon, 1975)

Examiner's Signature:

Date Considered:

Initial if reference was considered, whether or not citation is in conformance with MPEP. Mark through citation if not considered.
Include a copy of this citation form with your next correspondence to the Applicant(s).